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FUJIKURA YOSHIKI****(54) LIFT-UP SUPPRESSANT FOR CUTICLE****(57)Abstract:**

PROBLEM TO BE SOLVED: To obtain a lift-up suppressant for cuticle capable of effectively suppressing lift-up of cuticle originating from an anionic surfactant by including a material having buffer action capable of retaining pH of a system in a specific value in the case of jointly using with an anionic surfactant.

SOLUTION: The subject suppressant is obtained by including a material having buffer action capable of retaining pH (measured by a glass electrode method at 25° C) of a system at 3.5-5.5 in the case of jointly using with an anionic surfactant. An organic acid (salt) having 3.5-5.5 of pKa (in aqueous solution, at 25° C) is enumerated as a preferable buffer material, for example, the compound is capable of retaining pH of a system such as formulating with a hair cosmetic composition including ≥5.0 wt.% of an anionic surfactant, a system diluting the composition to a concentration of hair washing (diluting with 20 times of a diluent) and a system including an acid or base (for example, 0.0005-0.001 gram equivalent/L), at pH 3.5-5.5.